

Method of Manufacturing Reflective Mask Blank, and Reflective Mask Blank

ABSTRACT

A reflective mask blank including a substrate, a multilayer reflection film
5 consisting of at least two first layers and at least two second layers that are laminated
alternately and having different optical properties each other, and an absorber film are
manufactured by a sputtering method. Each layer is formed by two stages consisting of a
first stage applied from when the forming of each layer is started and until a prescribed
thickness is formed, and a second stage applied from when the prescribed thickness is
10 formed and until the forming of each layer is completed, and a sputtering pressure of the
first stage is set to higher than both a sputtering pressure at which the forming of the layer
formed just before is completed, and a sputtering pressure of the second stage.

[Fig. 1]